© EPODOC / EPO

PN - JP7074285 A 19950317

PD - 1995-03-17

PR - JP19940067127 19940405; JP19930080504 19930407

OPD - 1993-04-07

TI - SEMICONDUCTOR DEVICE

IN - YANAGIHARA MANABU:INOUE KAORU:ITO JUNJI:UNO TOMOAKI: ISHIKAWA OSAMU;OTA TOSHIMICHISAKAI HIROYUKI

PA - MATSUSHITA ELECTRIC IND CO LTD

IC - H01L23/12; H01L21/60; H01P3/08; H03F3/60

JP4273196 A [] CT - JP5037207 A [];

© WPI / DERWENT

- TI - High frequency semiconductor integrated circuit for millimetre wave band - has microstrip wiring board with dielectric film extending on ground conductor and metal wiring line extending on dielectric film
- PR - JP19930080504 19930407;JP19930192166 19930803:JP19930328236 19931224
- PN - JP7074285 A 19950317 DW199520 H01L23/12 012pp
 - US5510758 A 19960423 DW199622 H01P3/08 026pp
- PA - (MATU) MATSUSHITA DENKI SANGYO KK
 - (MATU) MATSUSHITA ELEC IND CO LTD
- IC - H01L21/58 ;H01L21/60 ;H01L23/12 ;H01P3/08 ;H03F3/60
- IN - FUJITA S; INOUE K; OTA Y; SAGAWA M; SAKAI H; TAKAHASHI K
- AB - J07074285 The device has a silicon or glass substrate provided with a contact hole (15) through which a grounding conductor (10) is connected to a microstrip wiring pattern (12-14). An interlayer insulating film (11) is placed between the wiring pattern and the grounding conductor.
 - The semiconductor chip (2) which contains the high frequency transistor is mounted onto the wiring pattern by means of solder bumps (40). The wiring pattern is supported by a lead frame β).
 - ADVANTAGE High frequency transistor allows device at cut-off frequency of 100 GHz. Allows high density mounting.
 - (Dwg.1/13)

OPD - 1993-04-07

AN - 1995-150504 [23]

© PAJ / JPO

PN JP7074285 A 19950317

none none

none none none

PD - 1995-03-17

AP - JP19940067127 19940405

IN - SAKAI HIROYUKI; others:06

PA - MATSUSHITA ELECTRIC IND CO LTD

TI - SEMICONDUCTOR DEVICE

 AB - PURPOSE:To realize a high performance submilimeter-millimeter wave semiconductor integrated circuit device having large application at low cost.

- CONSTITUTION:A ground conductor10, an interlayer insulation film 11, wiring conductors 12-14, and a contact hole 15 connecting the wiring conductor 14 and the ground conductor 10 are formed on a substrate 1 thus realizing a wiring board including a passive element and a transmission line. A semiconductor chip2 formed with a high frequency transistor is flip chip bonded to a microstrip wiring on the wiring board through a signal wiring20 and a bump 40 on the chip 2. This structure easily realizes a highly accurate microstrip wiring using a semiconductor process.
- H01L23/12 ;H01L21/60 ;H01P3/08 ;H03F3/60

none none none

